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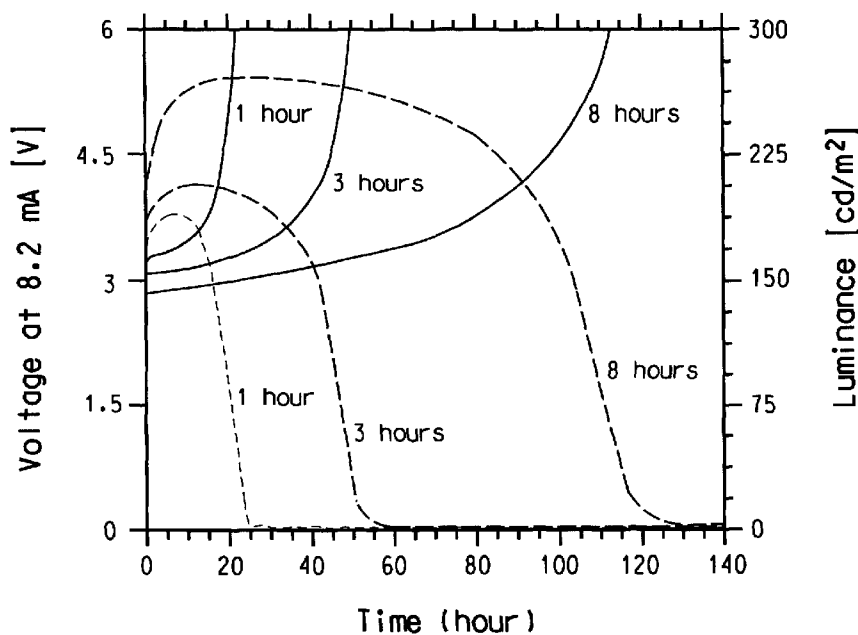
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(54) Title: HIGH RESISTANCE POLYANILINE BLEND FOR USE IN HIGH EFFICIENCY PIXELLATED POLYMER ELEC-
TROLUMINESCENT DEVICES



(57) Abstract: Compositions are provided comprising polyaniline (PANI) with poly(2-acrylamido-2-methyl-1-propanesulfonic acid) (PAAMPSA) as the counterion (PANI/PAAMPSA) and an amount of poly(styrenesulfonic acid) (PSS) sufficient to reduce the conductivity of the composition relative to PANI/PAAMPSA. Invention compositions may further comprise poly(acrylamide) (PAM). Invention compositions are useful as high resistance buffer layers for use in electroluminescent devices (such as, organic light emitting diodes (OLEDs)).

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